

CMOSIC 上 SiGe ミラーアレイ

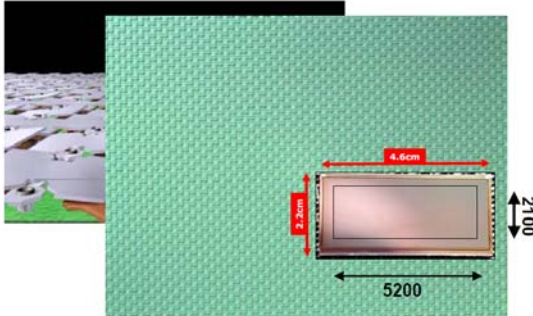
Ann Witvrouw

Exhibit #3: 11 megapixel micro-mirror array with 8 μm pitch made in poly-SiGe above standard 0.18 μm analog-CMOS wafers fabricated by NXP, featuring 6 interconnect levels.



11MPixel micro-mirror array

- To be used as SLM (Spatial Light modulator)

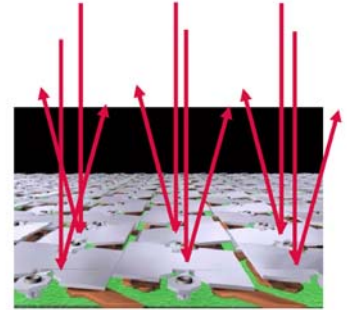


Project together with ASML, Bruco, NXP, Philips Appl. Tech.

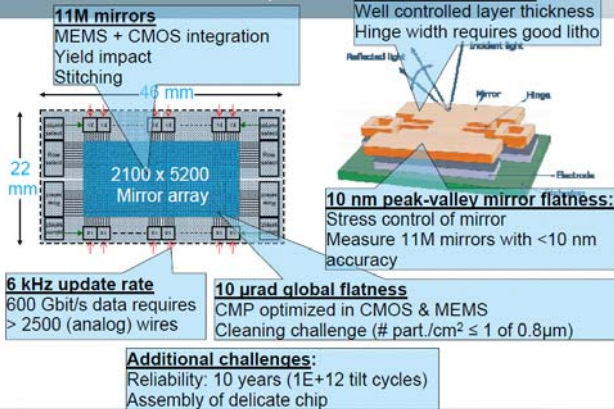
11MPixel micro-mirror array: application

Spatial Light Modulator:

- Light is deflected by each mirror to create image
- Applications: video projection, mask writing, maskless imaging



Micro-mirror array: Challenges



Micro-mirrors: State-of-the art

TI DLP Discovery 4000:

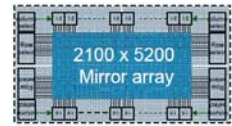
1920x1080 (2M)
Digital
Mirror Pitch 10.8 μm
Mirror Area 21 x 12 mm² (2.5 cm²)
<www.dlp.com

Fraunhofer SLM:

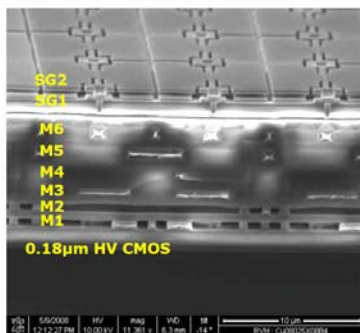
2048x512 (1M)
Analog
Mirror Pitch 16 μm
Mirror Area 33 x 8 mm² (2.6 cm²)
<www.ipms.fraunhofer.de

This work:

5200x2100 (11M)
Analog
Mirror Pitch 8 μm
Mirror area 42 x 17 mm²
(7 cm²)



Micro-mirrors: processing

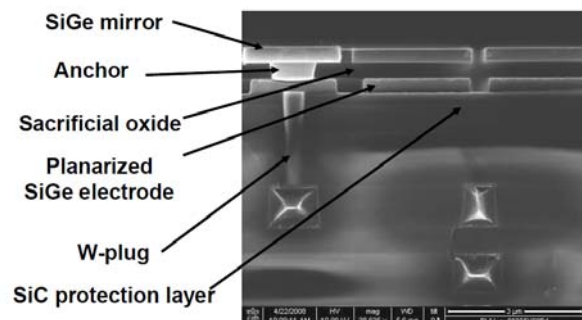


SiGe is chosen to achieve required mirror specs including reliability at CMOS-compatible T

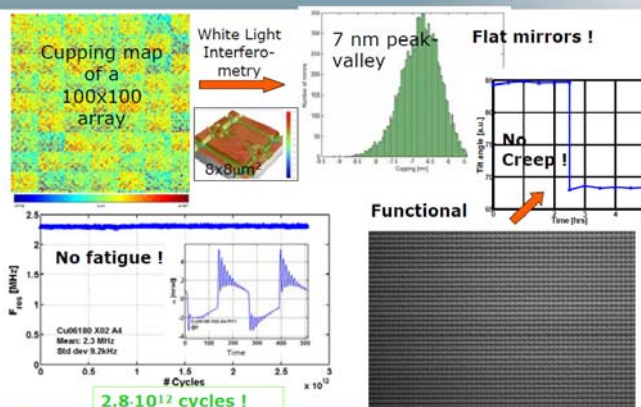
SiGe-based micro-mirror module
Planarised interface
0.18 μm analog CMOS with 6 metal levels (from NXP)

< L. Haspelagh et al.,
Proc IEDM 2008

Micro-mirrors: processing



Micro-mirrors: functional & reliability analysis



Micro-mirrors: packaging and testing

Mirror performance after packaging
123648 mirrors tested

Item	Specification	Results
Good Mirrors %	/	99.5 %
Mean Cupping	< 10 nm	5.4 nm
Residual Piston	< 1 nm	< 1 nm

Direct imaging:
3 mirror contact holes



Packaging and assembly
A. Witvrouw et al. Proc. MEMS09

Imaging results: J. Lauria et al.
Microel. Eng. 86, 569-572 (2009)

